EE 330
Lecture 9

IC Fabrication Technology

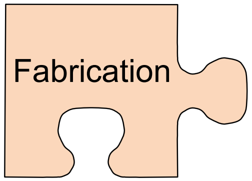
- Crystal Preparation
- Masking
- Photolithographic Process
- Deposition
- Ion Implantation
- Etching
- Diffusion
- Oxidation
- Epitaxy
- Polysilicon
- Planarization
- Contacts, Interconnect and Metalization

Exam 1 Friday Feb 18

Student Question: Why has Poly replaced aluminum for gates of transistors

- Want self-aligned
- Aluminum would melt during diffusion/annealing

The thin gate oxide under the gate acts as a mask for doping process preventing further doping under gate region (channel). So, this process makes the gate self-aligned with respect to the source and drain. As a result of all this, the source and drain do not extend under the gate. Thereby reducing Cgd and Cgs.
The doping process of the drain and source require very high temperature annealing methods (>800°C). If Al is used as a gate material, it would melt under such high temperature. This is because the melting point of Al is approximately 660°C.
But, if polysilicon is used as a gate material, it would not melt. Thus, the self-alignment process is possible with polysilicon gate.



Technology Files

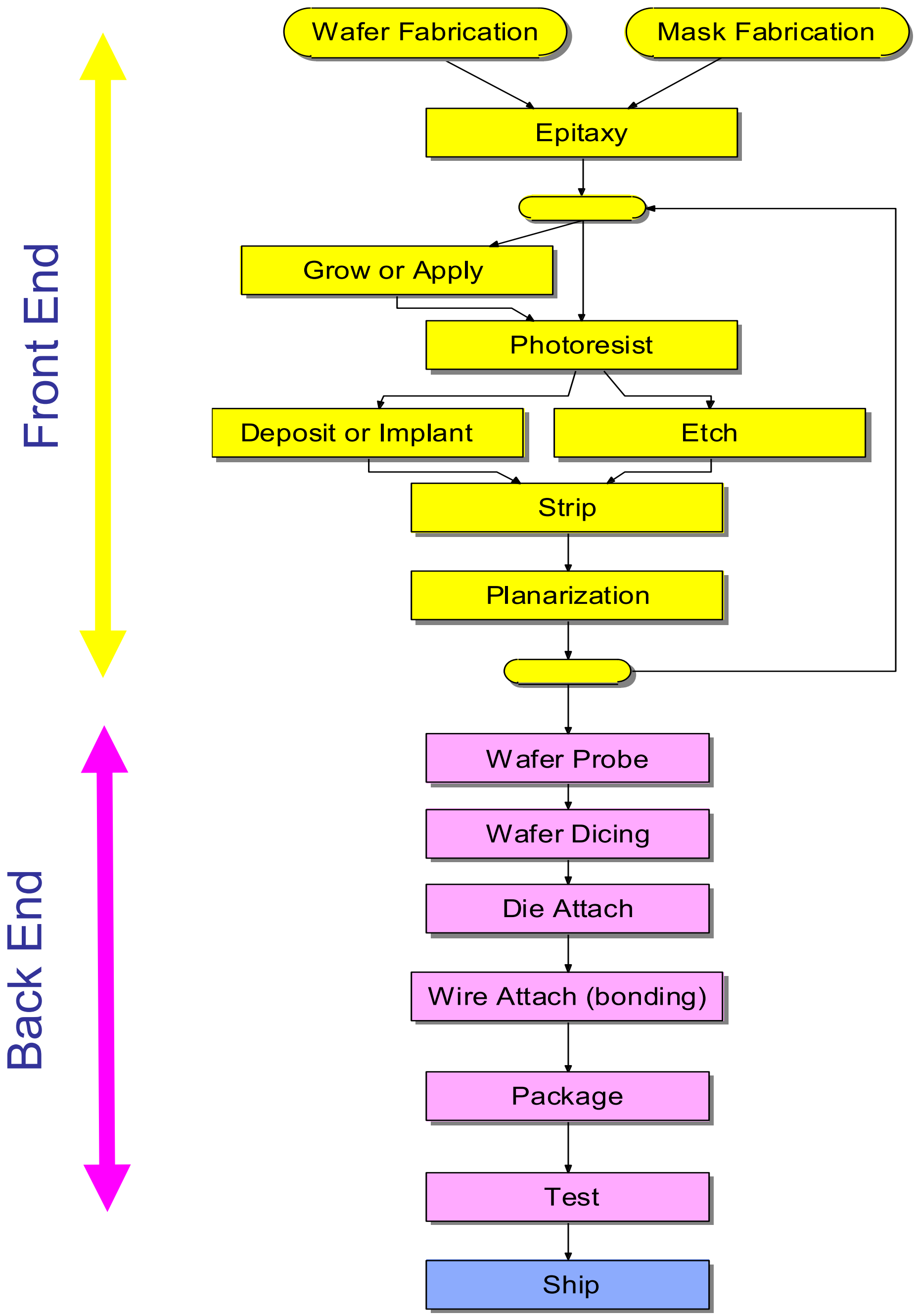
- Design Rules
- Process Flow (Fabrication Technology)
- Model Parameters (will discuss in substantially more detail after device operation and more advanced models are introduced)

IC Fabrication Technology

See Chapter 3 and a little of Chapter 1 of WH

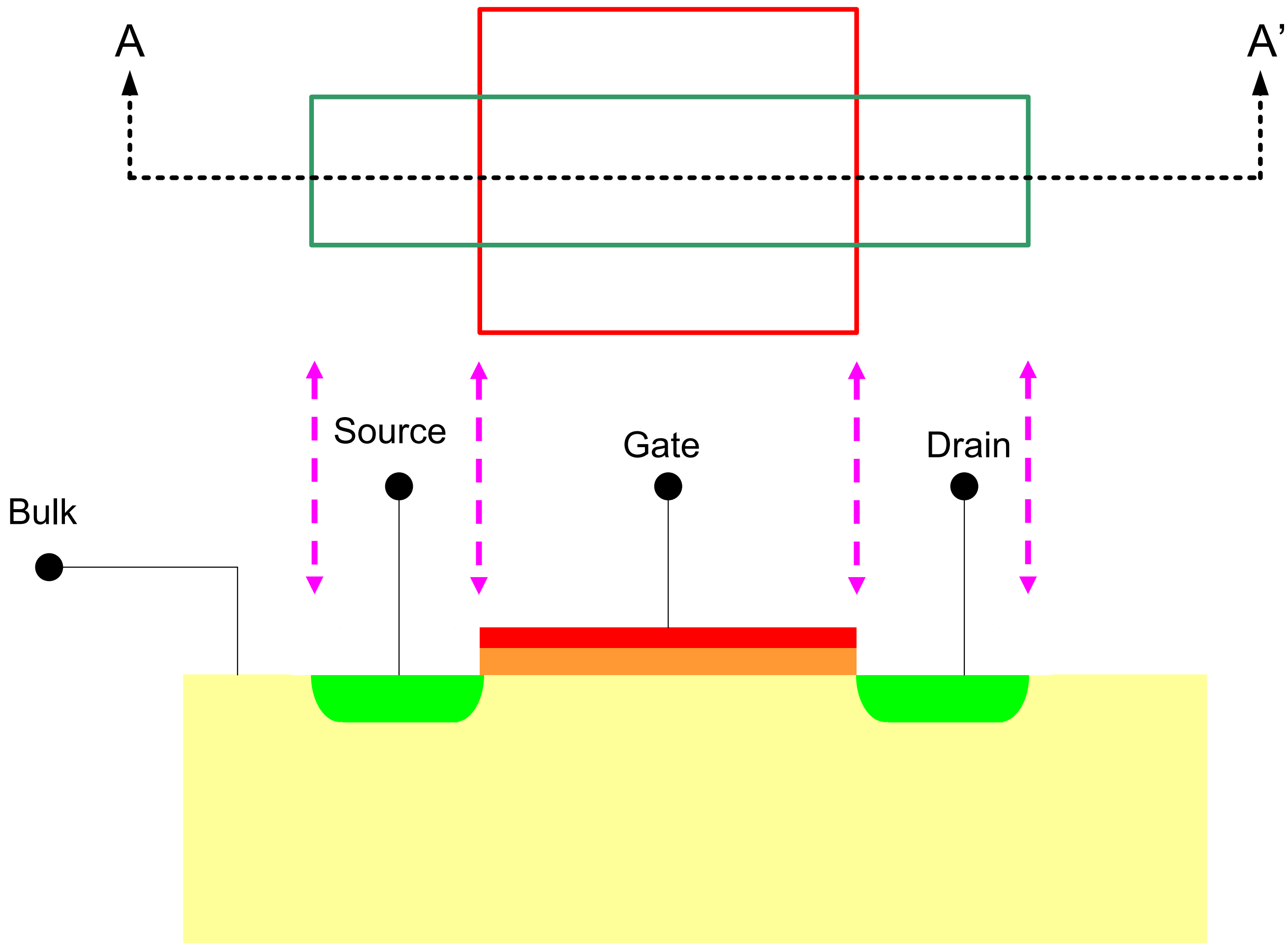
or Chapter 2 GAS for details

Generic Process Flow

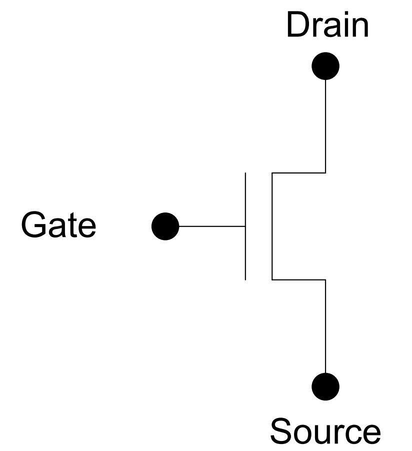


Recall

MOS Transistor

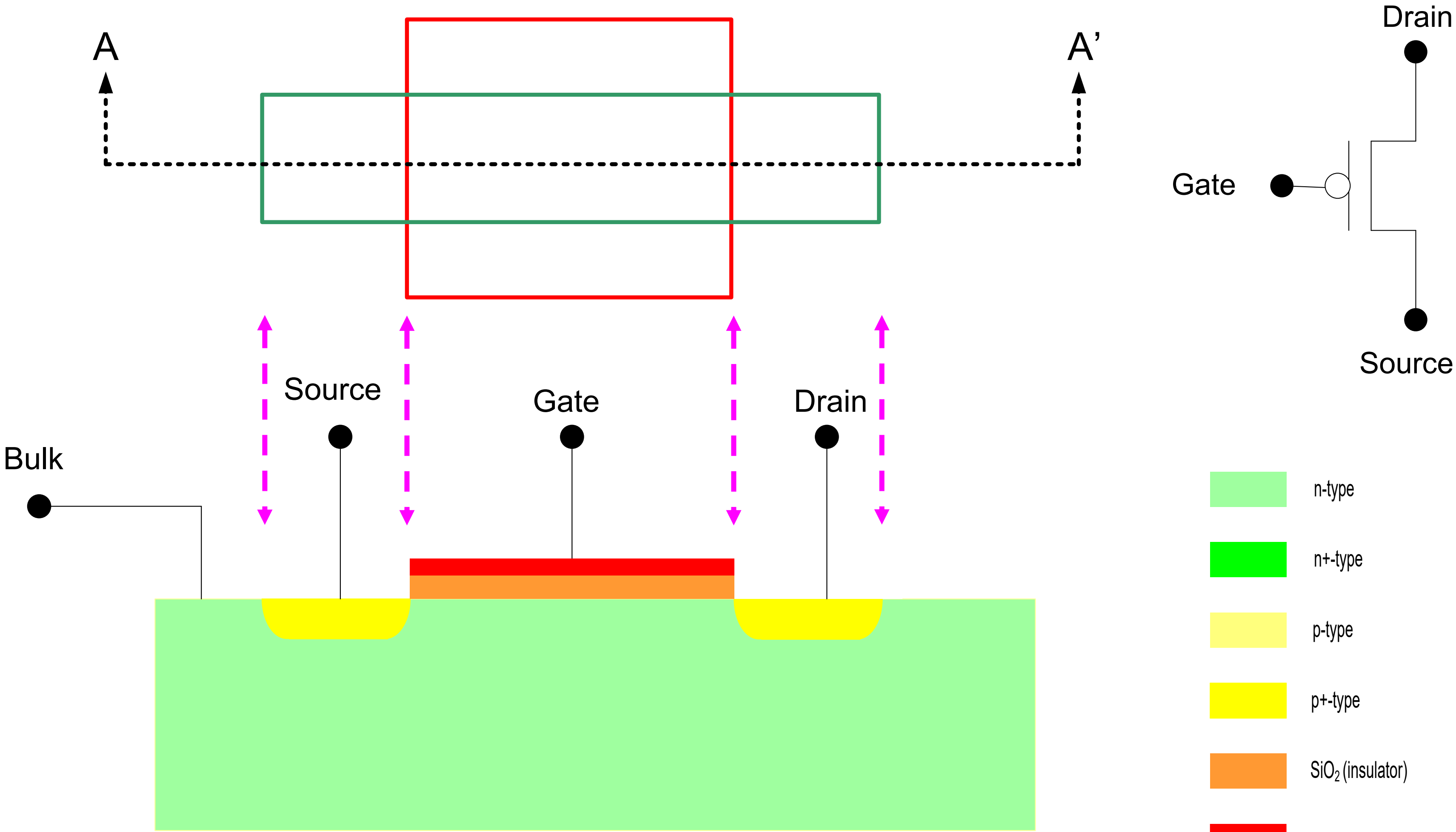


n-channel MOSFET



Review

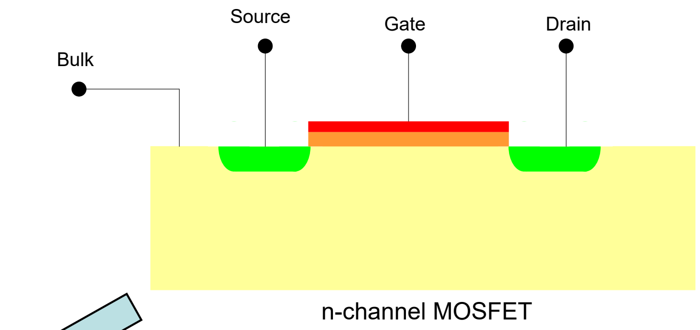
MOS Transistor

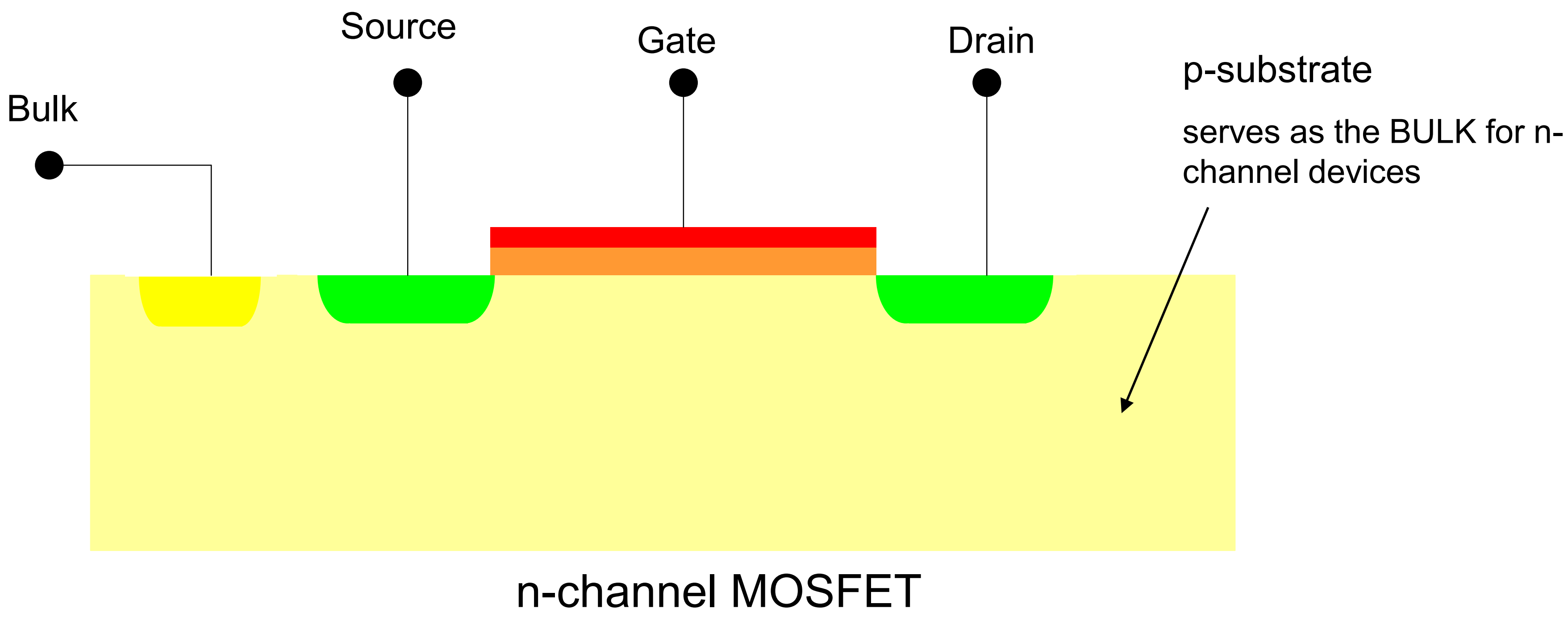


p-channel MOSFET

MOS Transistor

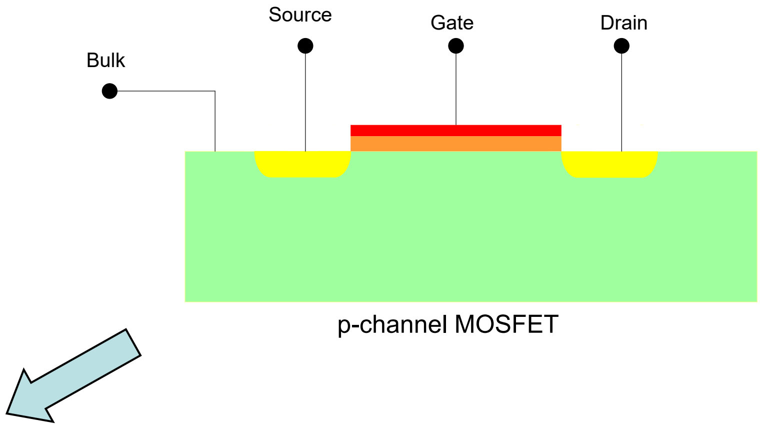
n-channel MOS transistor in Bulk CMOS n-well process with bulk contact

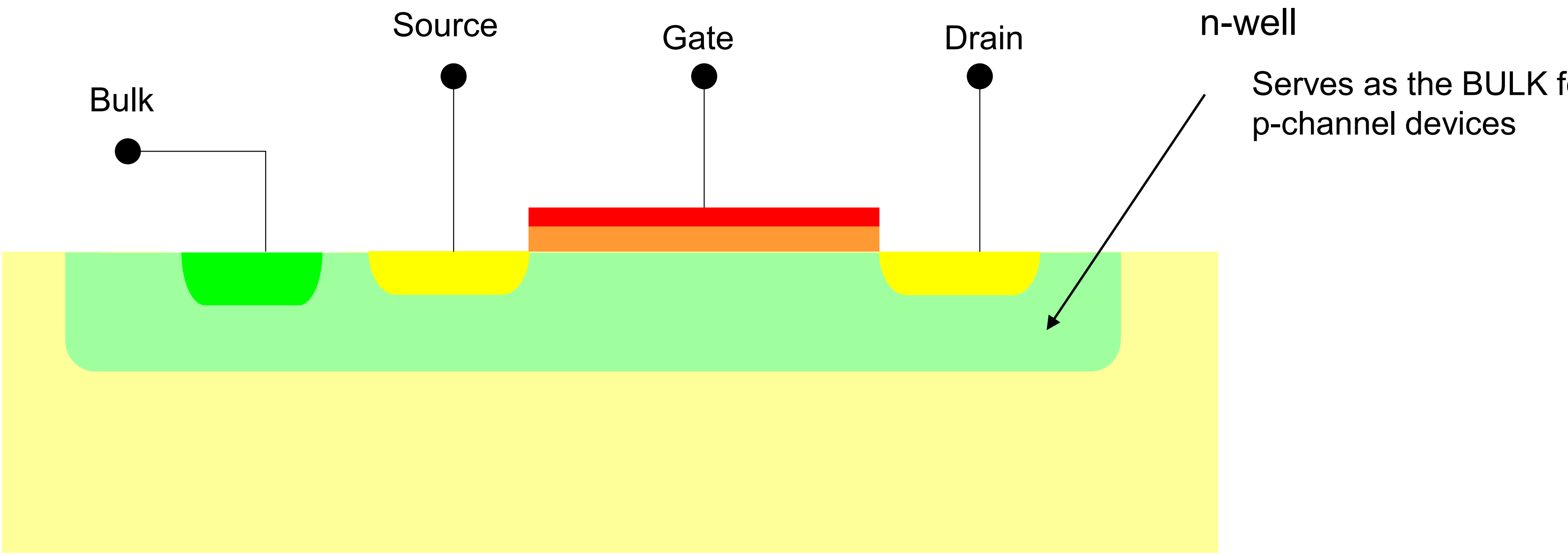




MOS Transistor

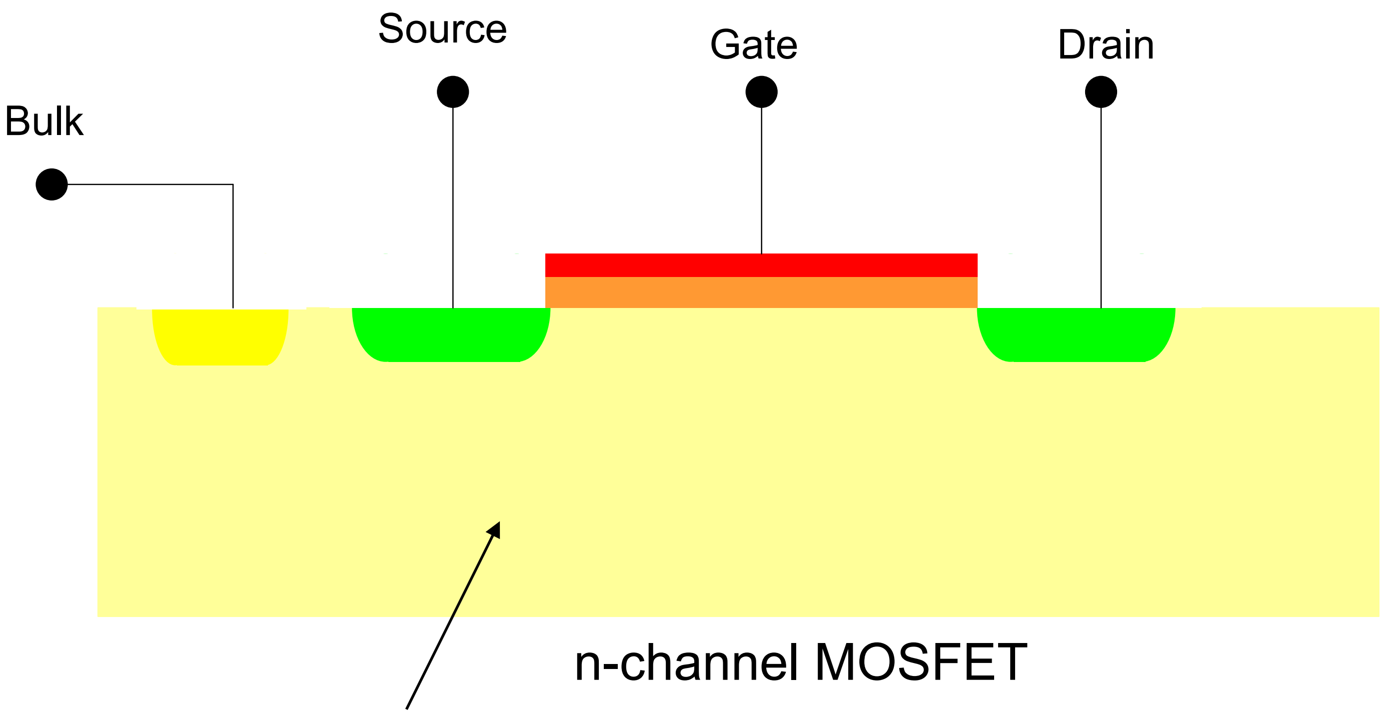
p-channel MOS transistor in
Bulk CMOS n-well process
with bulk contact and well (tub)





p-channel MOSFET

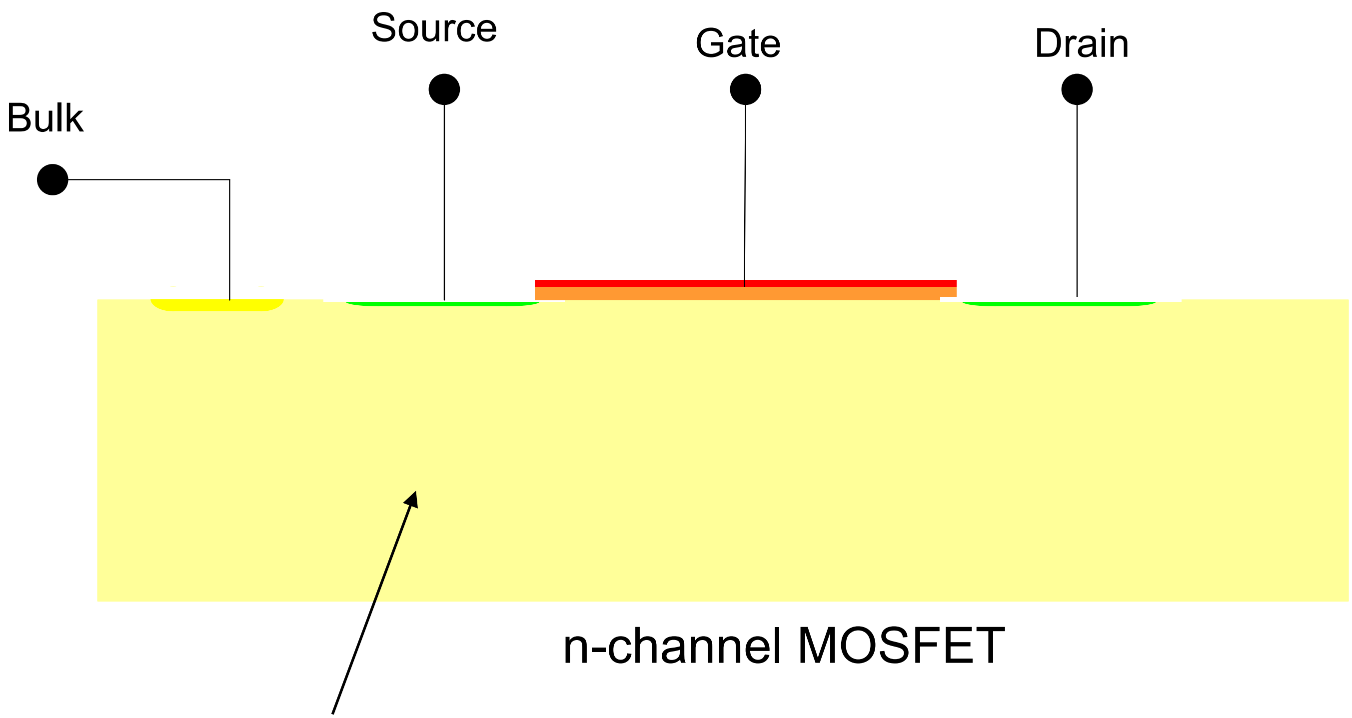
MOS Transistor



n-channel MOSFET

- Single-crystalline silicon
  - Serves as physical support member
  - Lightly doped
  - Vertical dimensions are not linearly depicted
  - Often termed the Bulk

MOS Transistor



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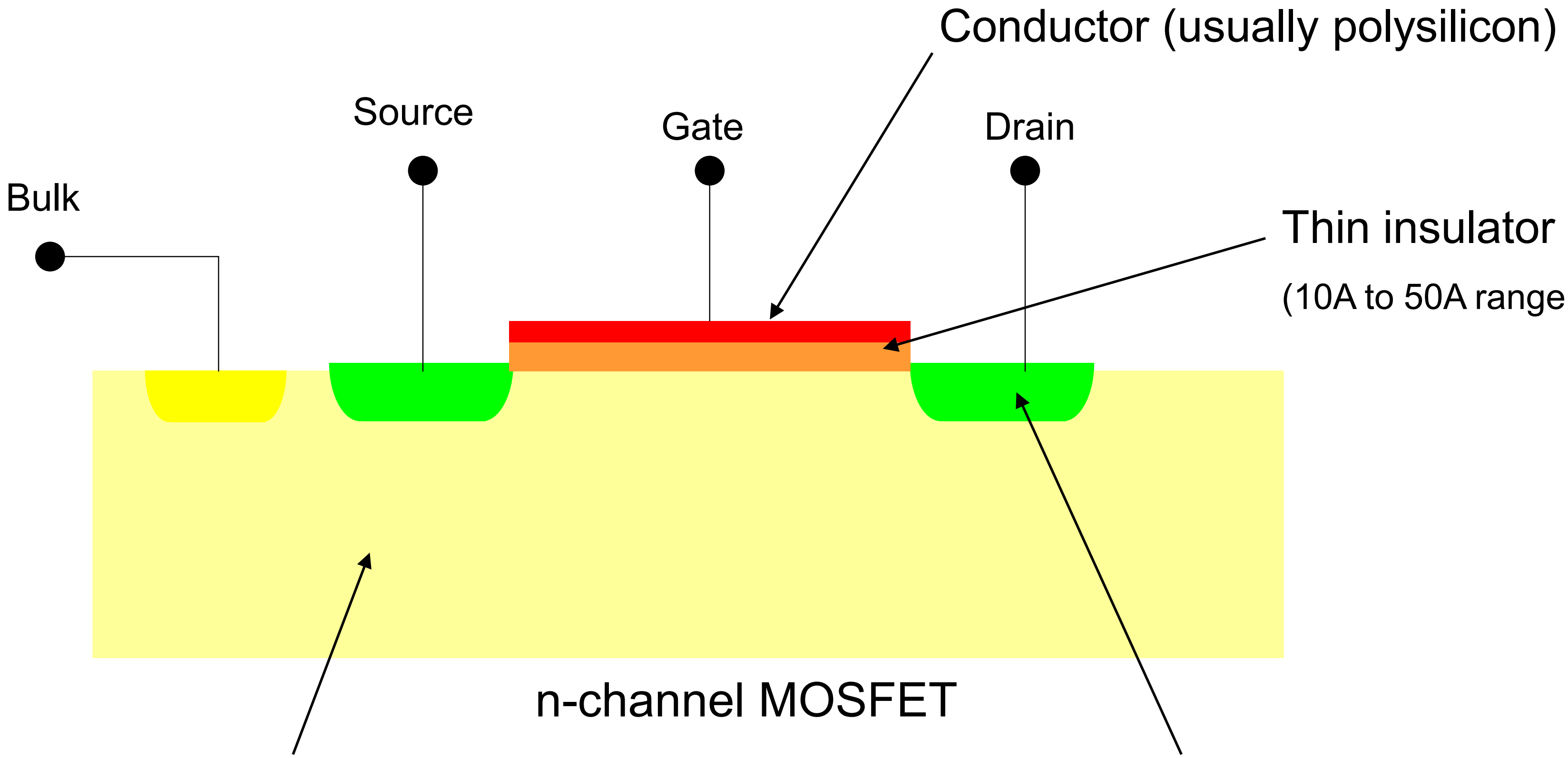
MOS Transistor

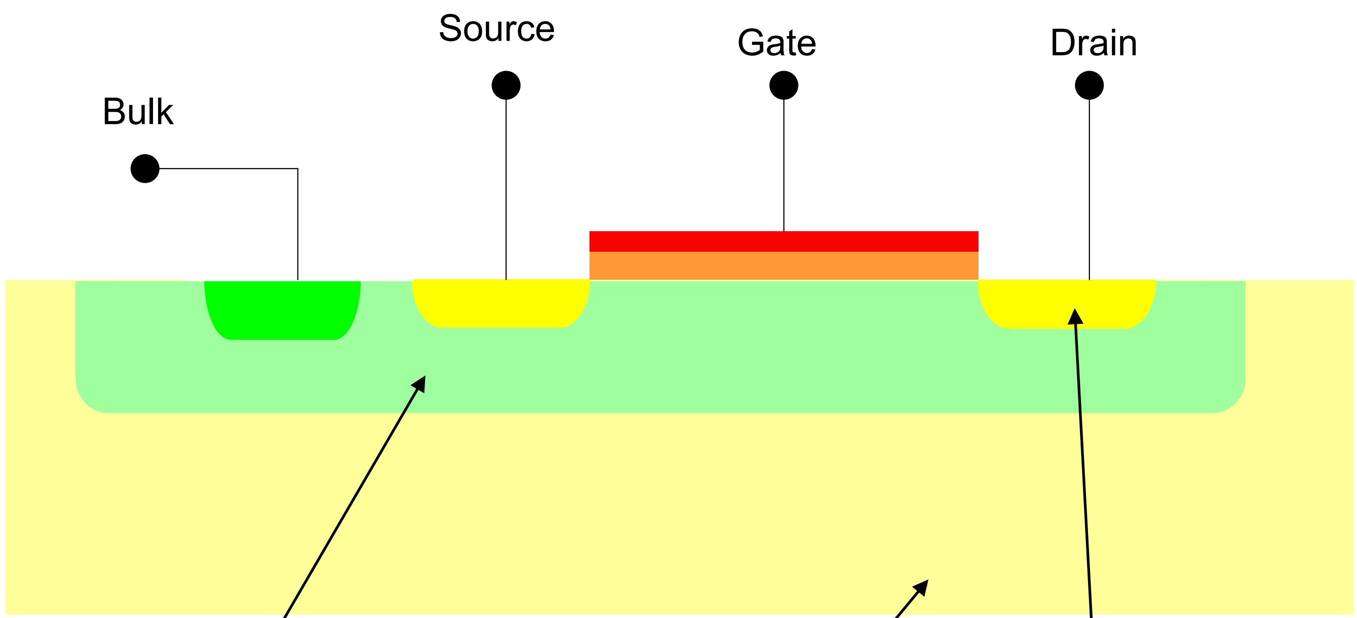


n-channel MOSFET

- Single-crystalline silicon
  - Serves as physical support member
  - Lightly doped (p-doping in the $10^{15}/cm^3$ range, silicon in the $2.2x10^{22}/cm^3$ range)
  - Vertical dimensions are not linearly depicted
  - Often termed the BULK

Dominant Doping Depicted – Generally Contain Prior Lower Density Dopants of Opposite Type

MOS Transistor



p-channel MOSFET

Lightly-doped n-type
($5x10^{16}/cm^3$ range)

More heavily-doped p-type
($10^{18}/cm^3$ range)

Lightly doped p-type
($10^{15}/cm^3$ range)

For Example: Drain Region Contains prior substrate p-dopants and n-type well dopants

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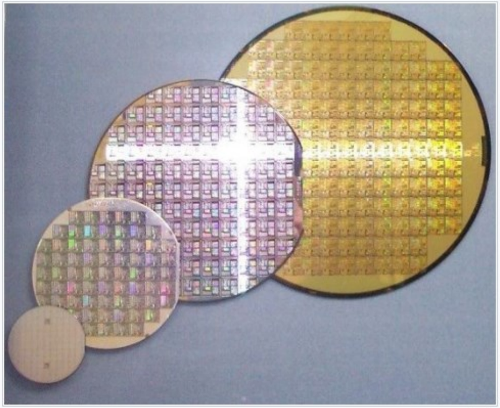
Crystal Preparation

- Large crystal is grown (pulled)
  - 12 inches (300mm) in diameter and 1 to 2 m long
  - Sliced to 250μm to 500μm thick
    - Prefer to be much thinner but thickness needed for mechanical integrity
  - 4 to 8 cm/hr pull rate
  - T=1430 ^{o}C
- Crystal is sliced to form wafers
- Cost for 12” wafer around $200
- 5 companies provide 90% of worlds wafers
- Somewhere around 400,000 12in wafers/month

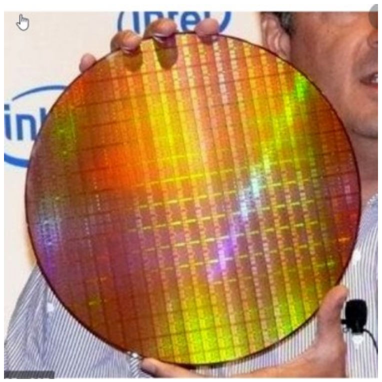
Crystal Preparation

Wafer size	Typical Thickness	Year Prodn [15]	Weight per wafer	100 mm2 (10 mm) Die per wafer [hide]
1-inch (25 mm)		1960		
2-inch (51 mm)	275 μm	1969		
3-inch (76 mm)	375 μm	1972		
4-inch (100 mm)	525 μm	1976	10 grams [19]	56
4.9 inch (125 mm)	625 μm	1981		
150 mm (5.9 inch, usually referred to as "6 inch")	675 μm	1983		
200 mm (7.9 inch, usually referred to as "8 inch")	725 μm.	1992	53 grams [19]	269
300 mm (11.8 inch, usually referred to as "12 inch")	775 μm	2002	125 grams[19]	640
450 mm (17.7 inch) (proposed).[20]	925 μm	future	342 grams [19]	1490
675-millimetre (26.6 in) (Theoretical).[21]	Unknown.	future		

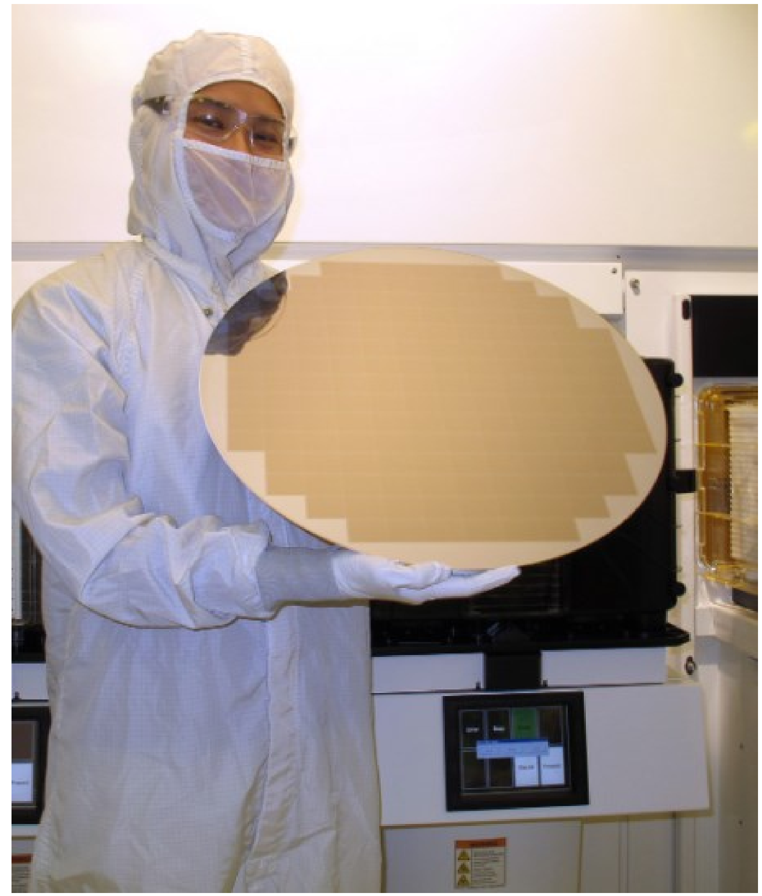


2-inch (51 mm), 4-inch (100 mm), 6-inch (150 mm), and 8-inch (200 mm) wafers

Crystal Preparation

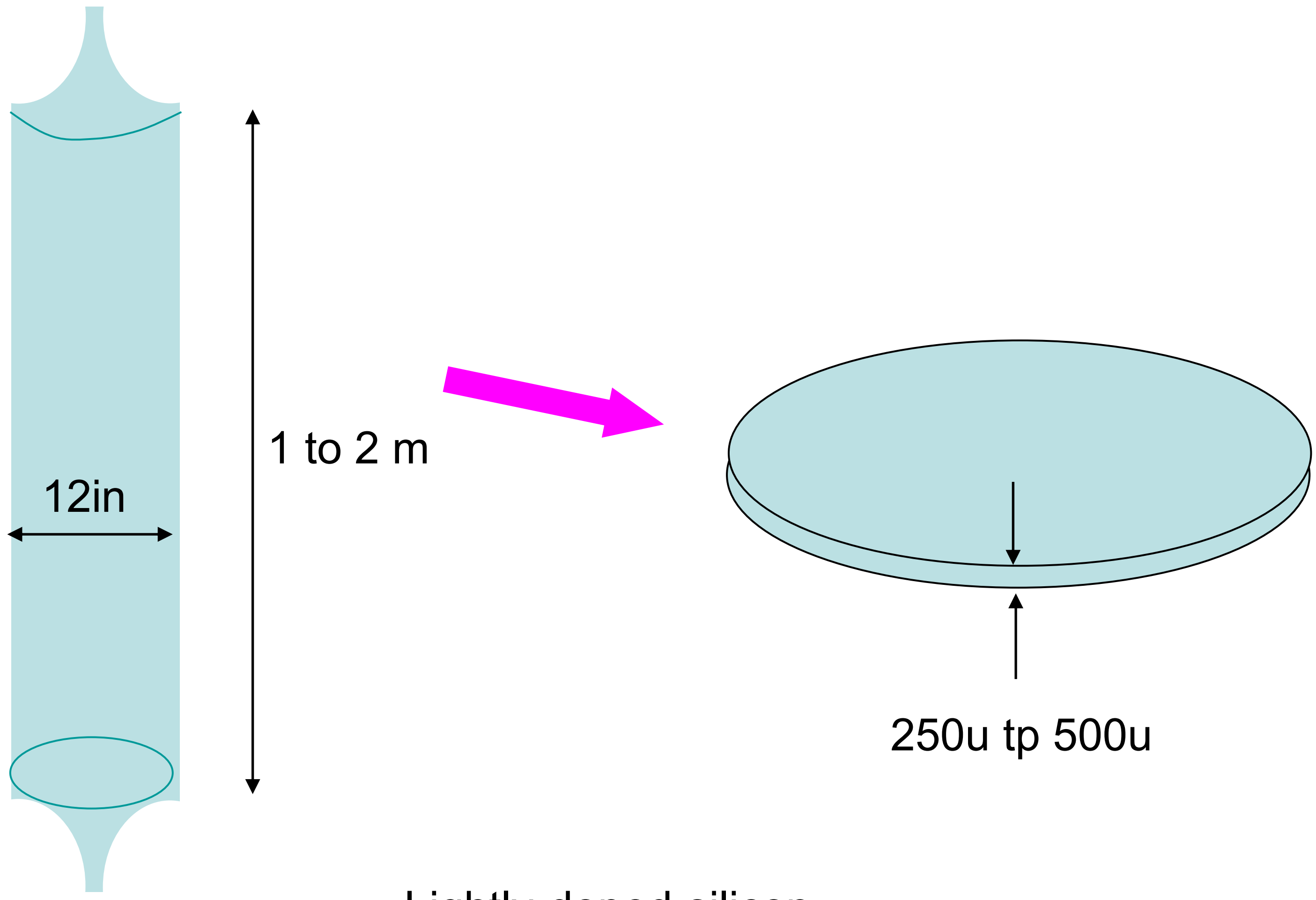


300mm wafer



450 mm wafer

Crystal Preparation



Some predict newer FABs to be at 450mm (18in) by 2020 but appears to be uncertain whether it will ever happen

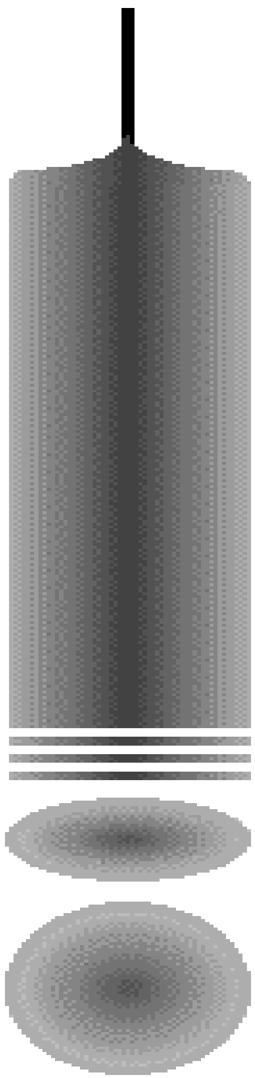
Lightly-doped silicon
Excellent crystalline structure

Crystal Preparation

Return on Investment Essential to Make Transition

200mm (8”) and 300mm (12”) are dominant in production today

Crystal Preparation

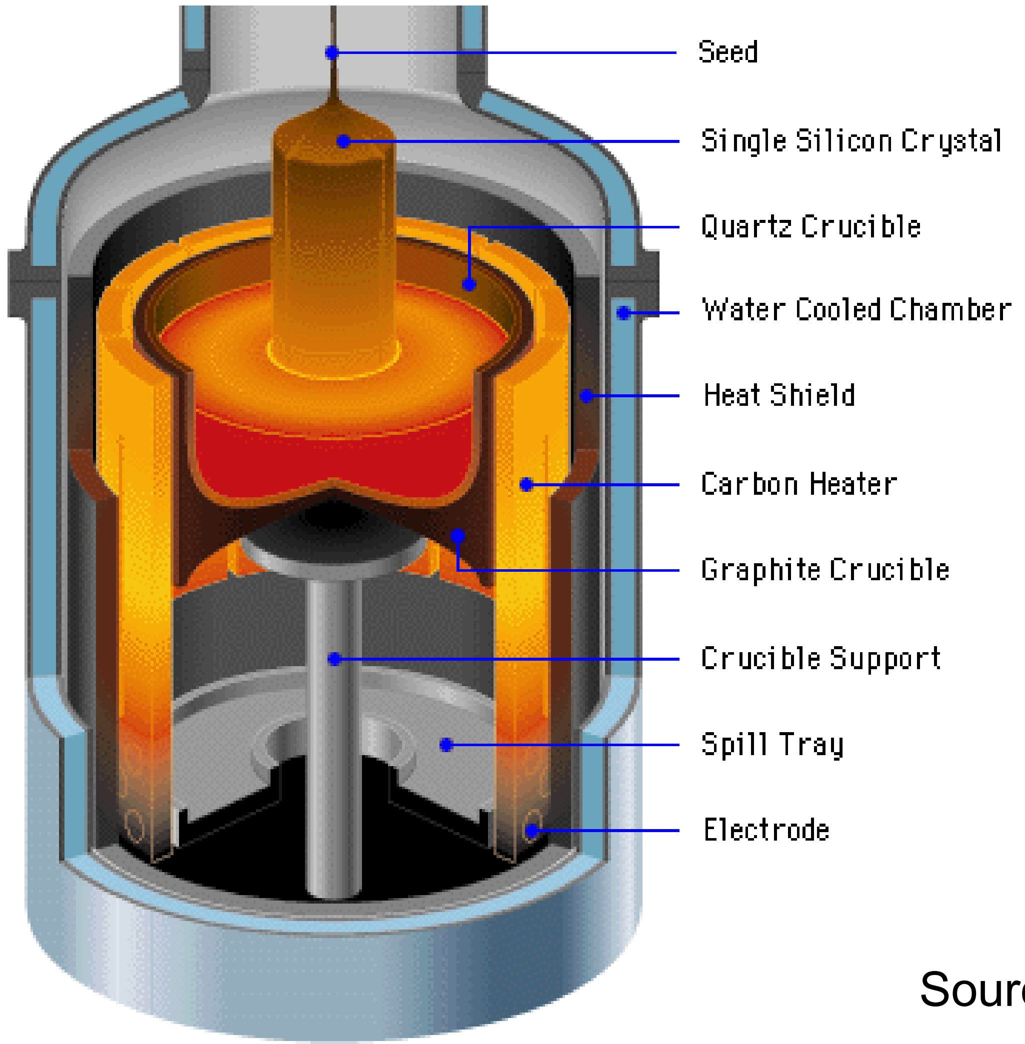


From www.infras.com

Crystal Preparation

Source: WEB

Crystal Preparation



Source: WEB

Crystal Preparation

Source: WEB

Crystal Preparation

A section of 300mm ingot is loaded into a wiresaw

Source: WEB

Crystal Preparation

Source: WEB

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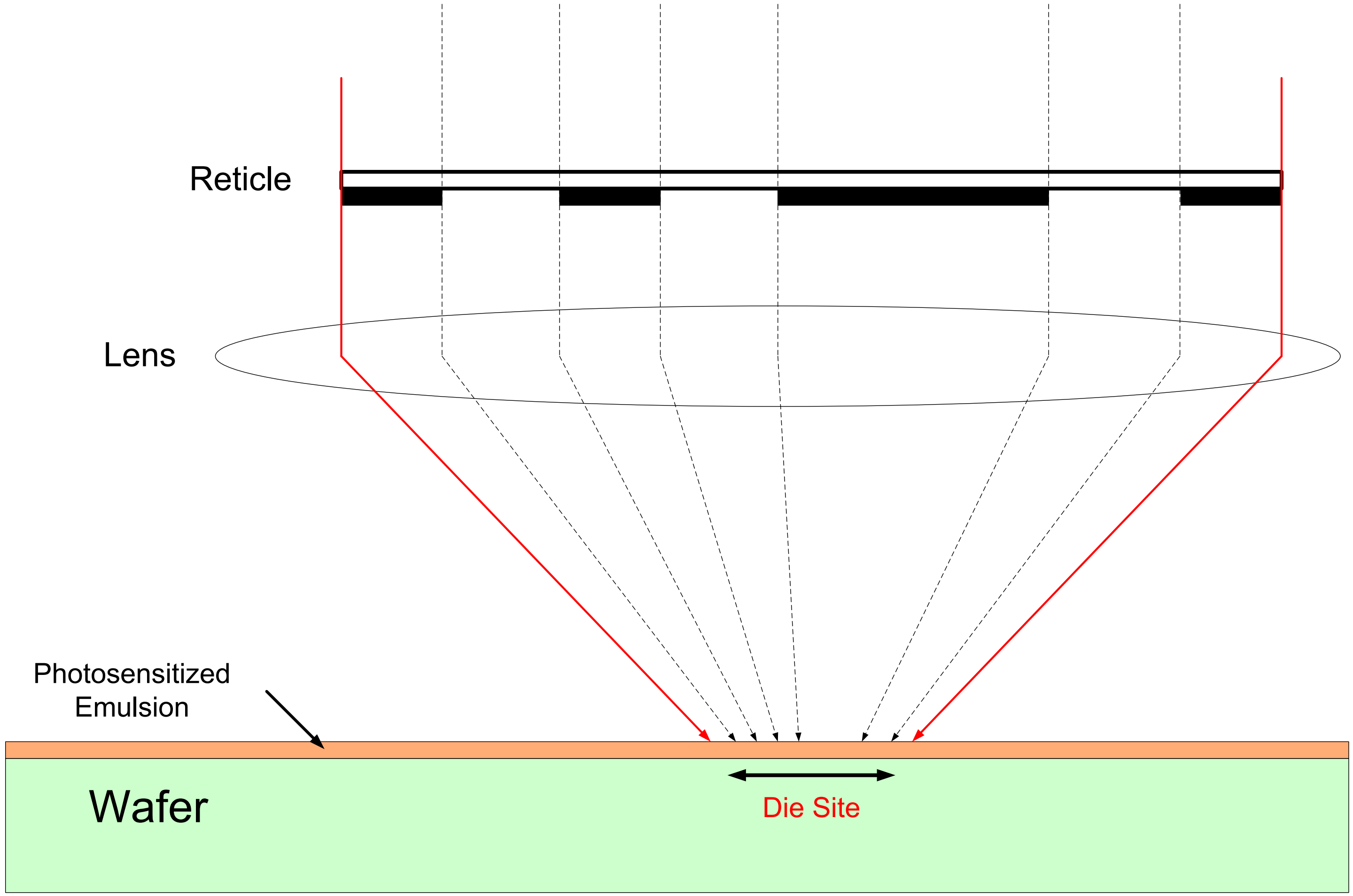
Masking

- Use masks or reticles to define features on a wafer
  - Masks same size as wafer
  - Reticles used for projection
  - Reticle much smaller (but often termed mask)
  - Reticles often of quartz with chrome
  - Quality of reticle throughout life of use is critical
  - Single IC may require 20 or more reticles
  - Cost of “mask set” now exceeds $1million for state of the art processes
  - Average usage 500 to 1500 times
  - Mask costs exceeding 50% of total fabrication costs in sub 100nm processes
  - Serve same purpose as a negative (or positive) in a photographic process
  - Usually use 4X optical reduction - exposure area approx. 860mm^2

    (now through 2022 ITRS 2007 litho, Table LITH3a)

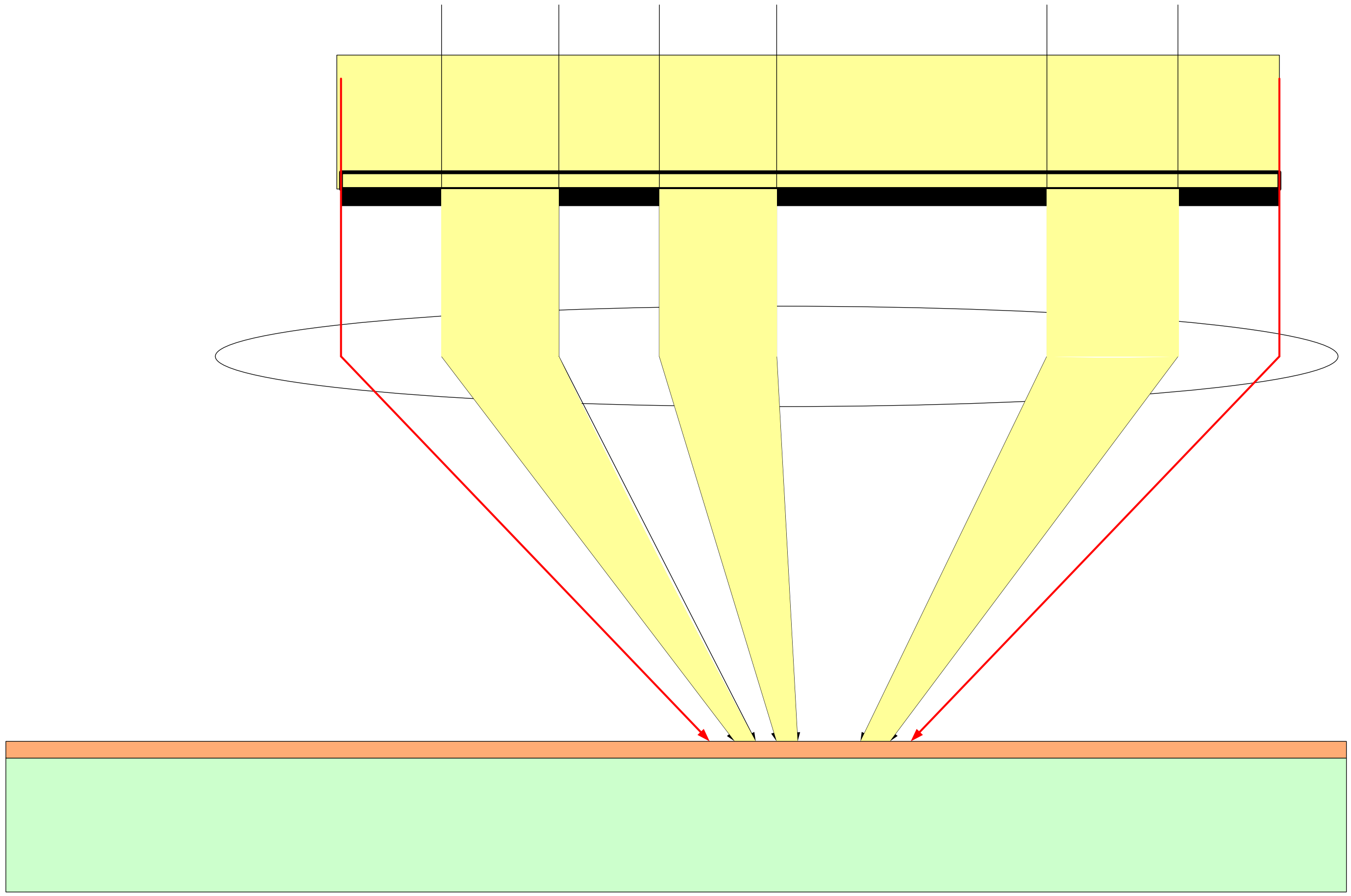
Masking



Step and Repeat (stepper) used to image across wafer

Masking

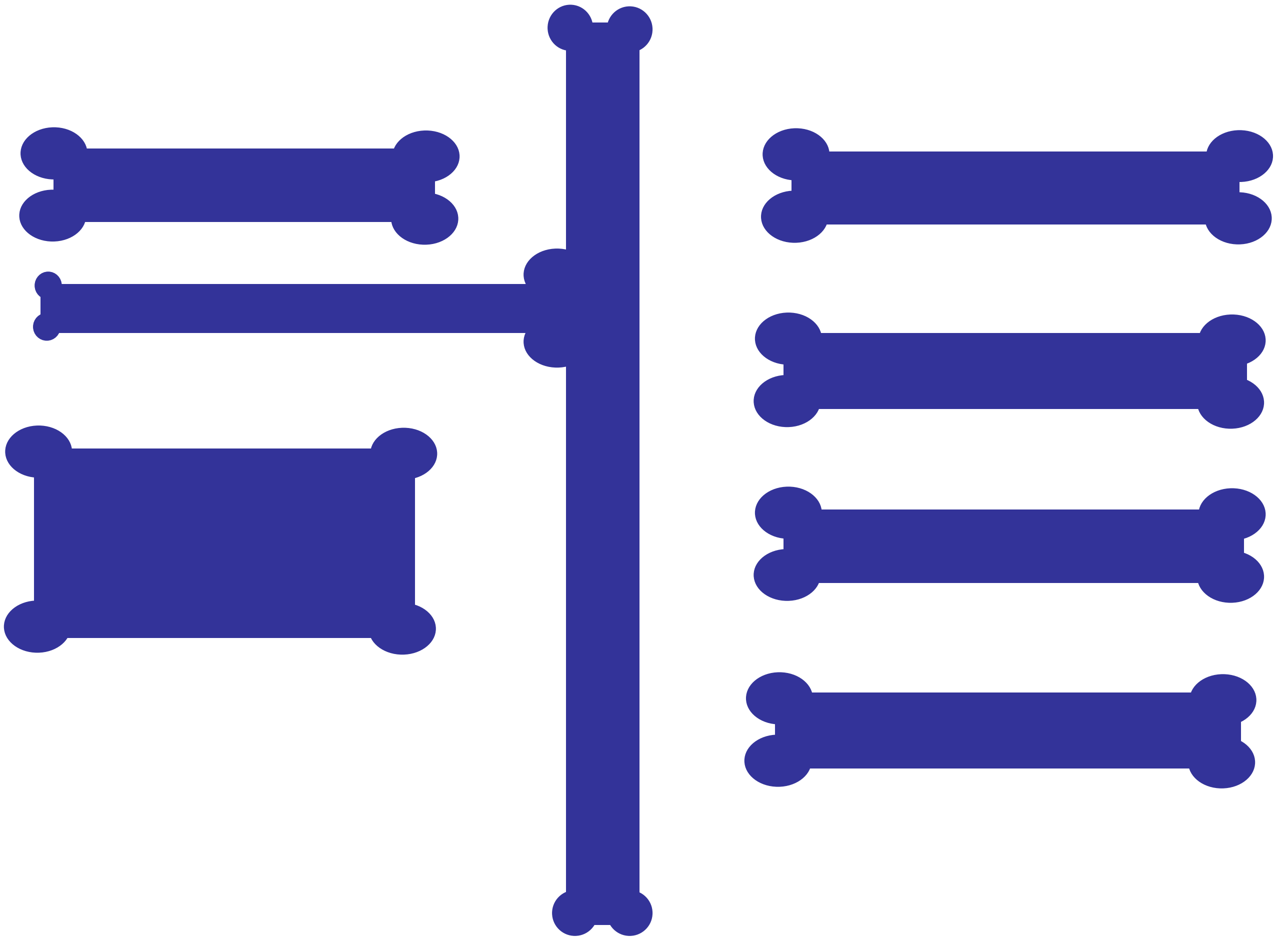
Exposure through reticle



Masking

Mask Features

Masking



Mask Features Intentionally Distorted to Compensated For Wavelength Limitations in Small Features

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Photolithographic Process

- Photoresist
  - Viscous Liquid
  - Uniform Application Critical (spinner)
  - Baked to harden
  - Approx 1u thick
  - Non-Selective
  - Types
    - Negative – unexposed material removed when developed
    - Positive-exposed material removed when developed
    - Thickness about 450nm in 90nm process (ITRS 2007 Litho)
- Exposure
  - Projection through reticle with stepper (scanners becoming popular)
  - Alignment is critical !!
  - E-Bean Exposures
    - Eliminate need fro reticle
    - Capacity very small

Stepper: Optics fixed, wafer steps in fixed increments
Scanner: Wafer steps in fixed increments and during exposure both optics and wafer are moved to increase effective reticle size

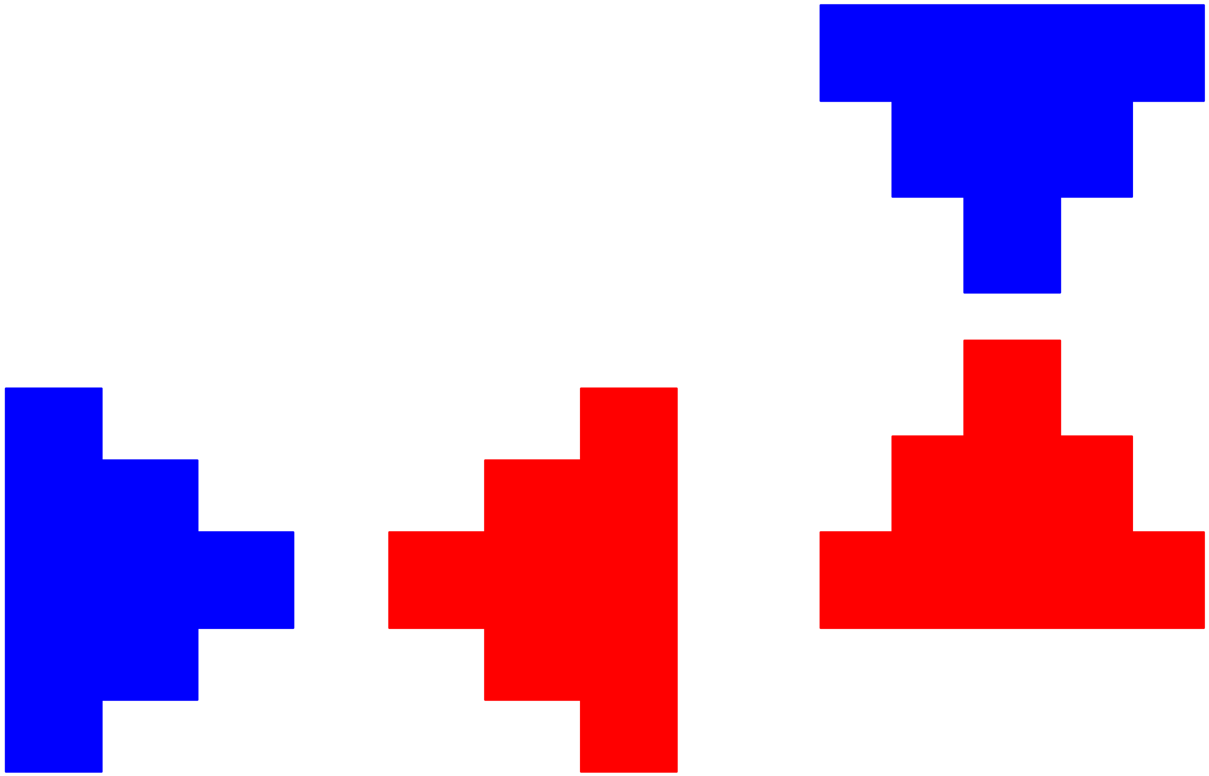
Steppers

Stepper costs in the $10M range with thru-put of around 100 wafers/hour

Steppers

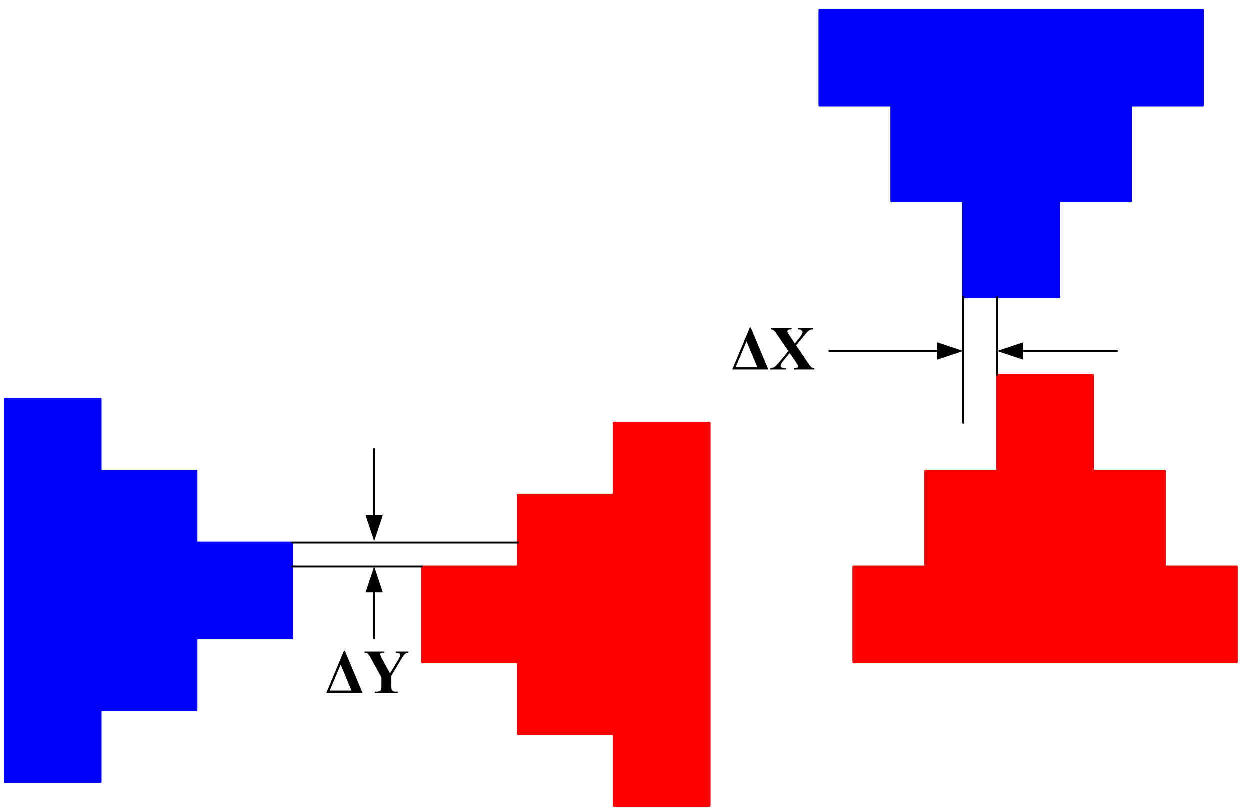
Mask Alignment

Correctly Aligned



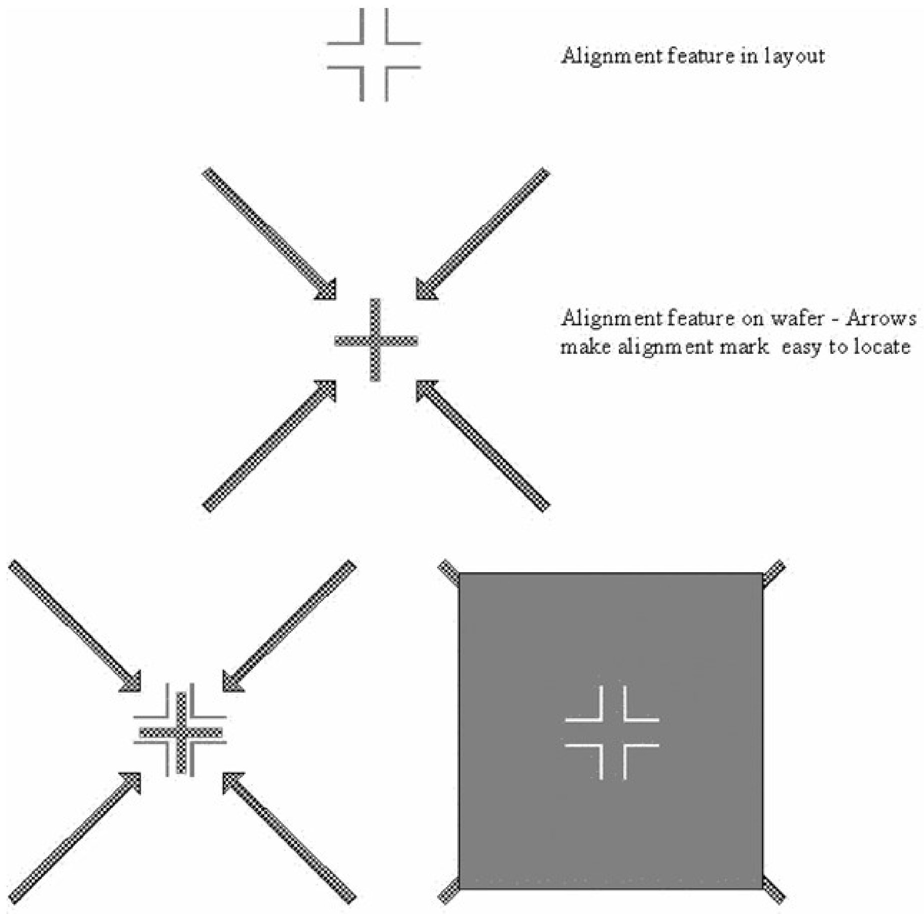
Mask Alignment

Alignment Errors



Mask Alignment

Other alignment marks (http://www.mems-exchange.org/users/masks/intro-equipment.html)



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Deposition

- Application of something to the surface of the silicon wafer or substrate
  - Layers 15A to 20u thick
- Methods
  - Physical Vapor Deposition (nonselective)
    - Evaporation/Condensation
    - Sputtering (better host integrity)
  - Chemical Vapor Deposition (nonselective)
    - Reaction of 2 or more gases with solid precipitate
    - Reduction by heating creates solid precipitate (pyrolytic)
  - Screening (selective)
    - For thick films
    - Low Tech, not widely used today

Deposition

Example: Chemical Vapor Deposition

Silane (SiH_4) is a gas (toxic and spontaneously combustible in air) at room temperature but breaks down into Si and H_2 above 400^{o}C so can be used to deposit Si.

$$S_iH_4 \rightarrow S_i + 2H_2$$

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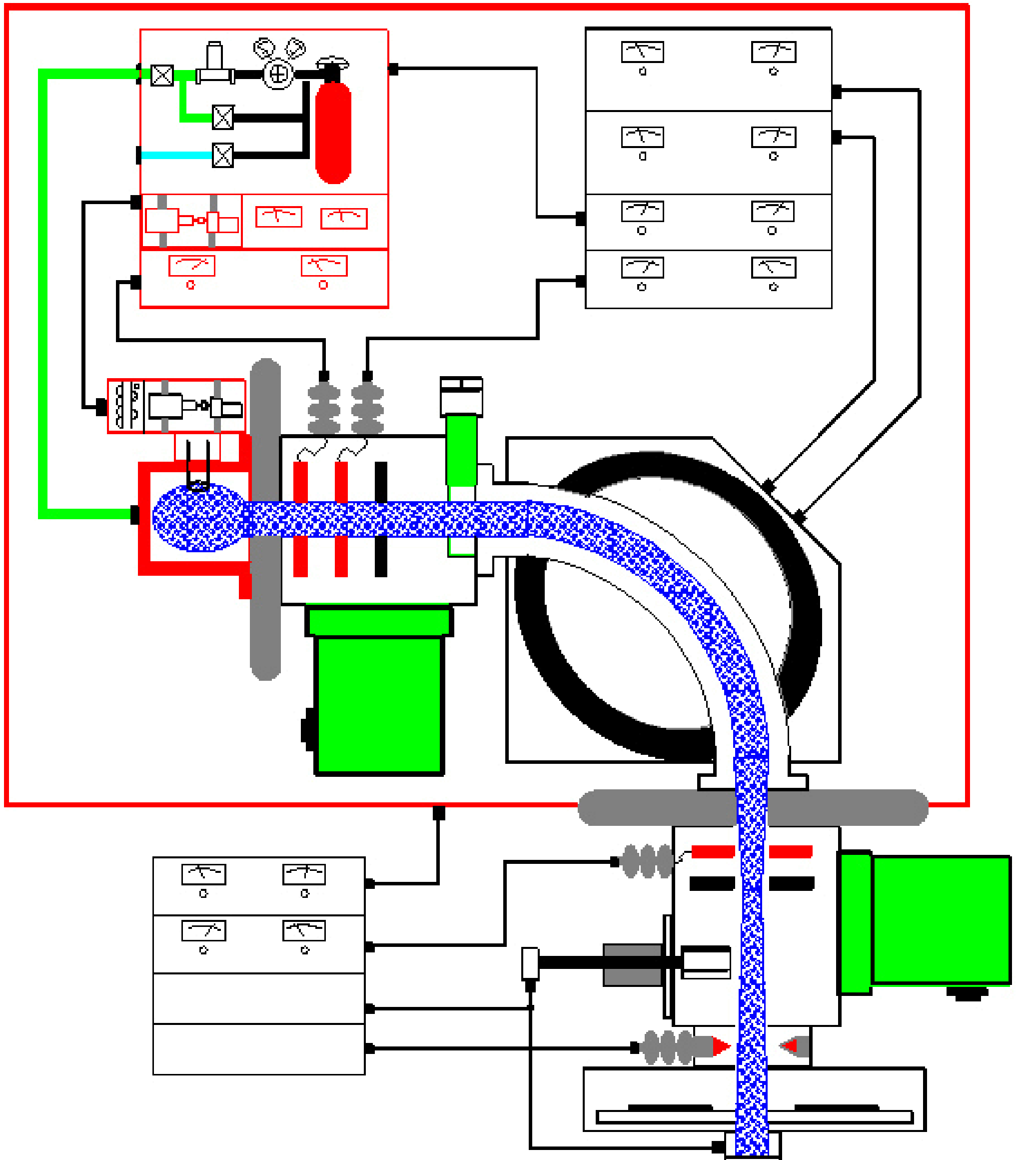
Ion Implantation

Application of impurities into the surface of the silicon wafer or substrate

- Individual atoms are first ionized (so they can be accelerated)
- Impinge on the surface and burry themselves into the upper layers
- Often very shallow but with high enough energy can go modestly deep
- Causes damage to target on impact
- Annealing heals most of the damage
- Very precise control of impurity numbers is possible
- Very high energy required
- High-end implanters considered key technology for national security

Ion Implantation Process



From http://www.casetechnology.com/implanter

Ion Implanter

From http://www.casetechnology.com/implanter

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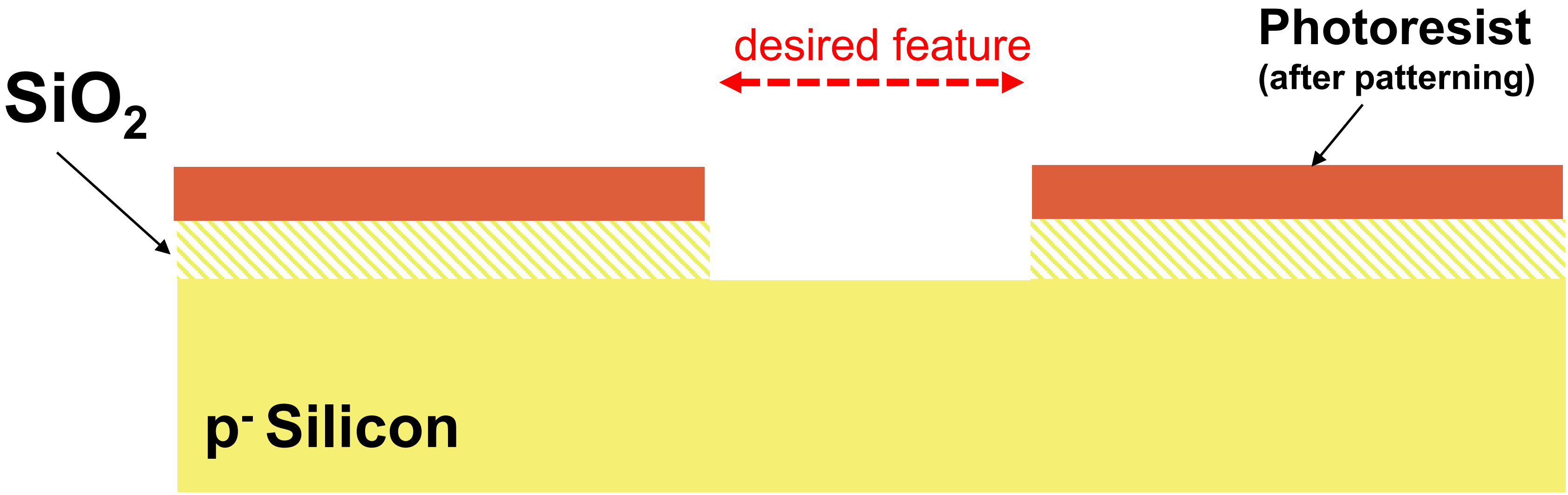
Etching

Selective Removal of Unwanted Materials

- Wet Etch
  - – Inexpensive but under-cutting a problem
- Dry Etch
  - – Often termed ion etch or plasma etch

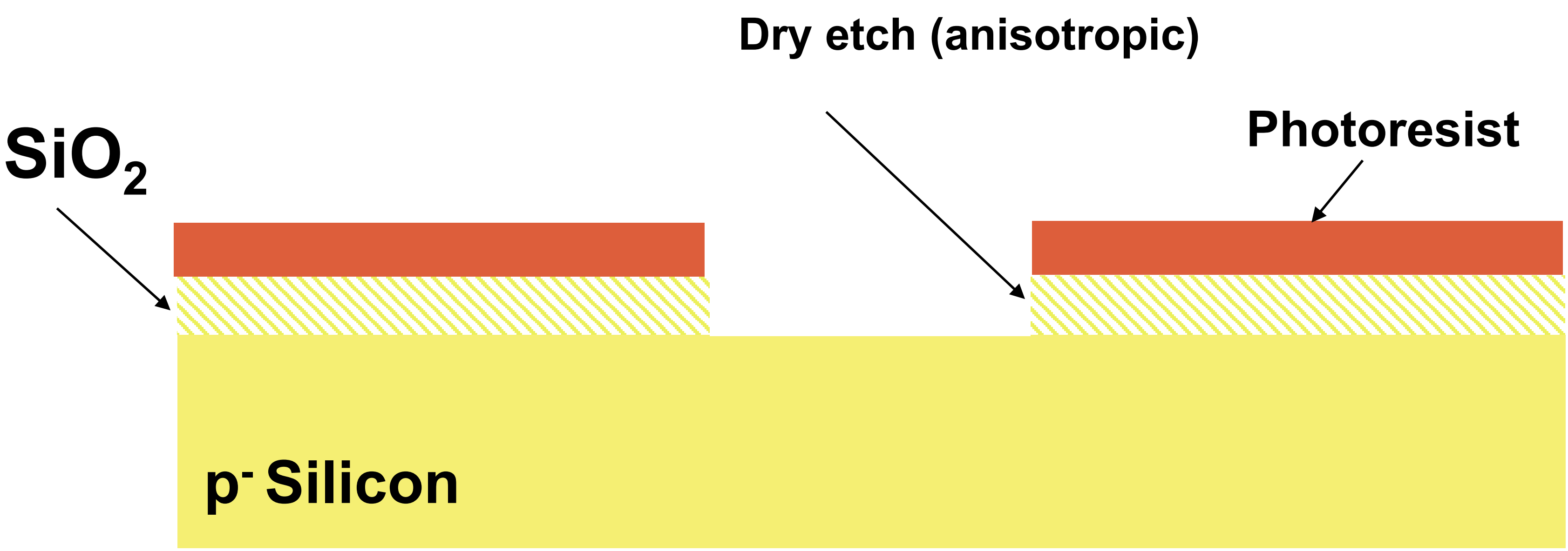
Etching



Desired Physical Features

Note: Vertical Dimensions in silicon generally orders of magnitude smaller than lateral dimensions so different vertical and lateral scales will be used in this discussion. Vertical dimensions of photoresist which is applied on top of wafer is about ½ order of magnitude larger than lateral dimensions

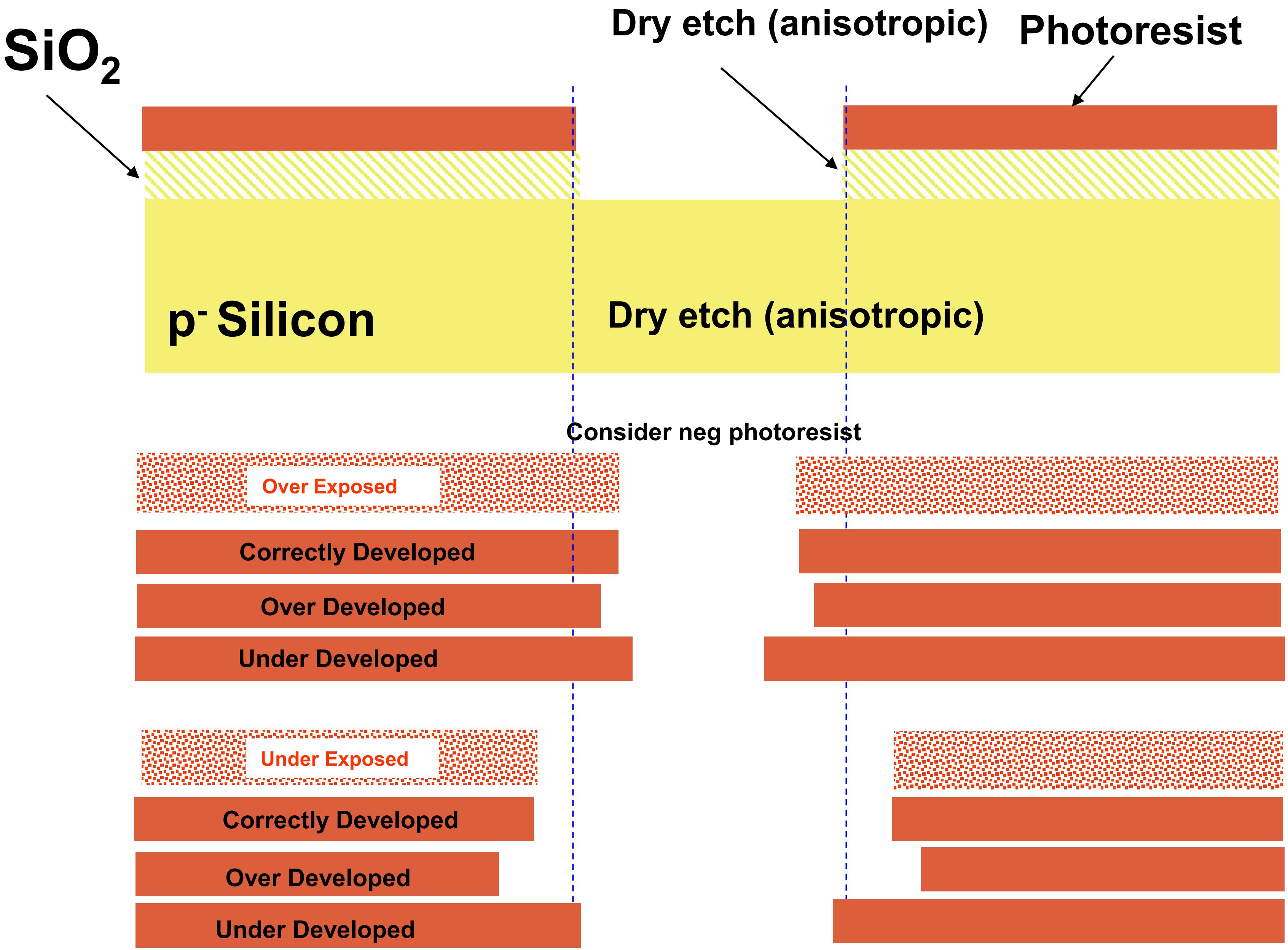
Etching



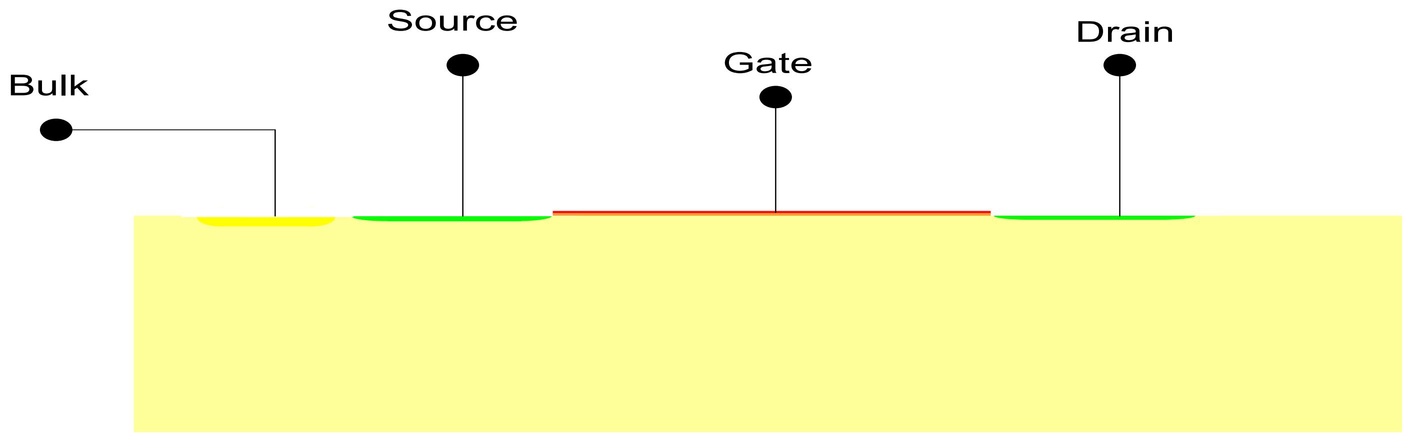
Desired Physical Features

Dry Etch can provide very well-defined and nearly vertical edges (relative to photoresist paterning)

Etching (limited by photolitghographic process)



Lateral Relative to Vertical Dimensions

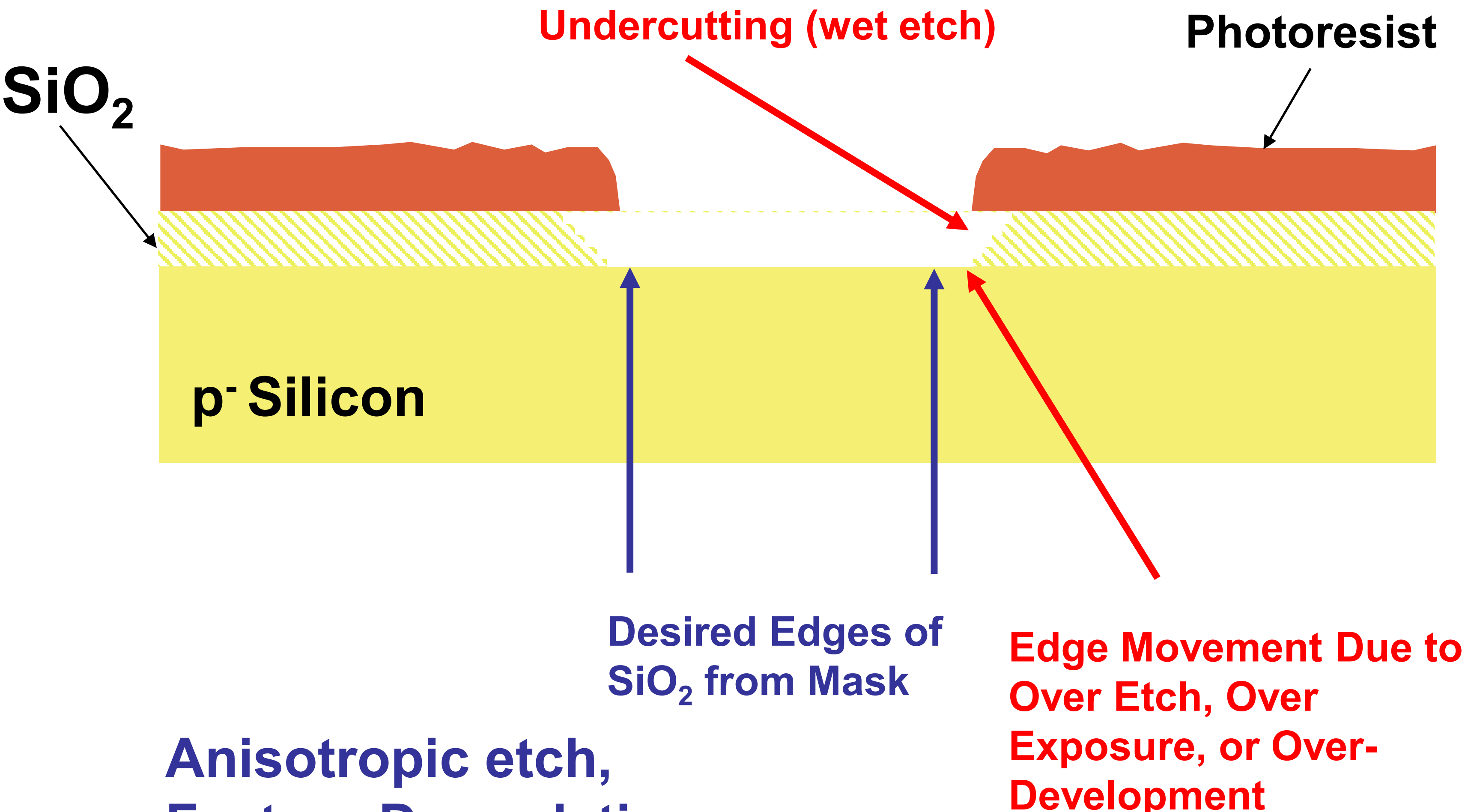


n-channel MOSFET

Still Not to Scale

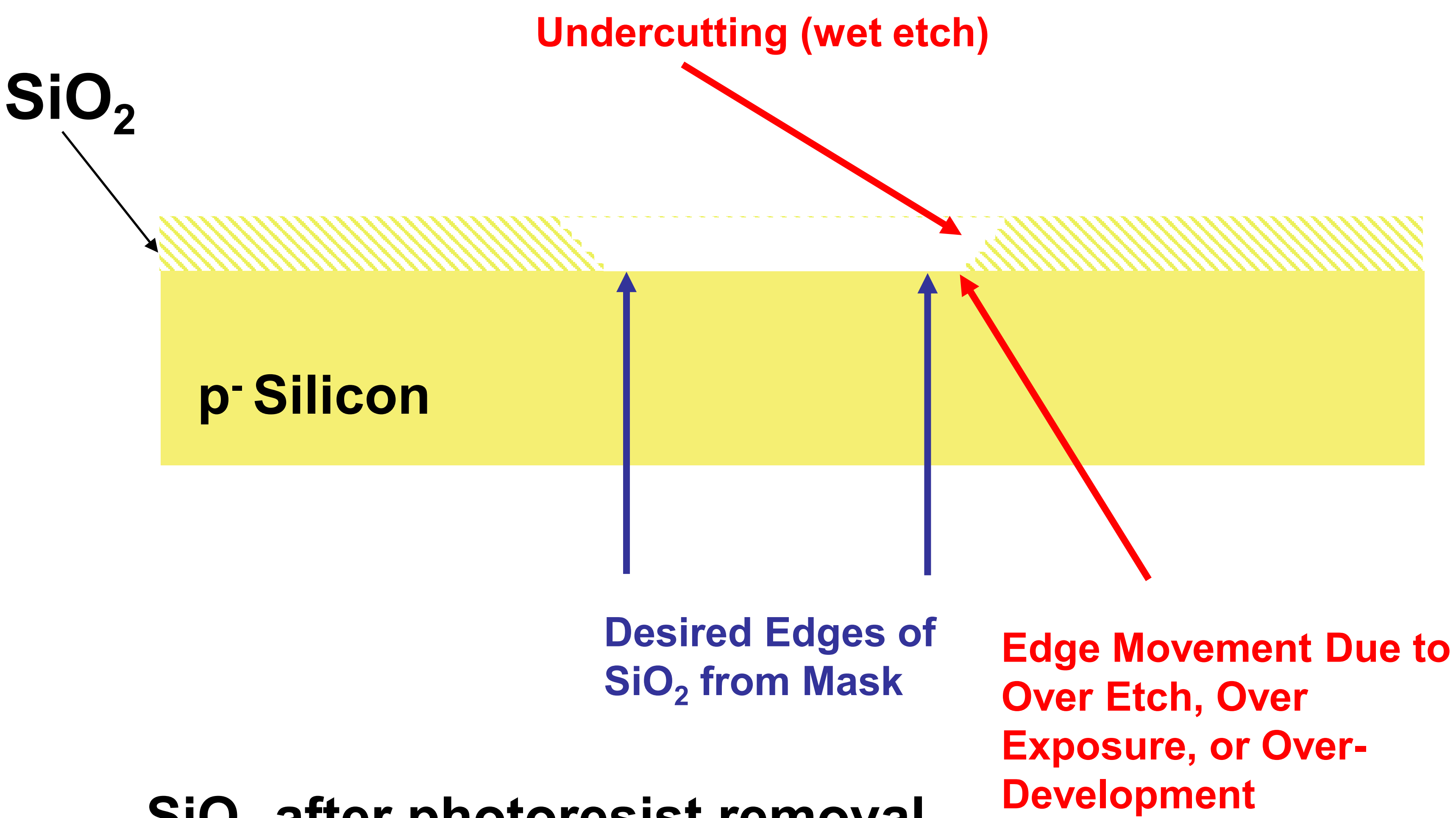
For Example, the wafer thickness is around 250u and the gate oxide is around 50A (5E-3u) and diffusion depths are around λ/5

Etching



Anisotropic etch, Feature Degradation

Etching



SiO_2 after photoresist removal

Stay Safe and Stay Healthy !

End of Lecture 9